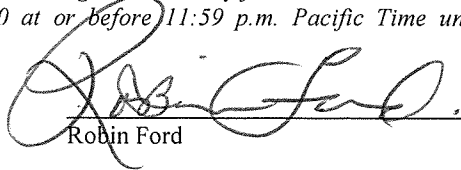


PATENT
RESPONSE UNDER 37 CFR 1.116
EXPEDITED PROCEDURE
EXAMINING GROUP 1795

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

I hereby certify that this correspondence is being electronically filed with the United States Patent and Trademark Office on February 3, 2010 at or before 11:59 p.m. Pacific Time under the Rules of 37 CFR § 1.8.


Robin Ford

Appl No. : 10/587,194 Confirmation No. 8444
Applicant : Jean-Louis Stehle
Filed : July 24, 2006
Title : PROTECTED PATTERN MASK FOR REFLECTION LITHOGRAPHY
IN THE EXTREME UV OR SOFT X-RAY RANGE

TC/A.U. : 1795
Examiner : Jonathan G. Jelsma

Docket No. : 58059/N75

Customer No. : 23363

AMENDMENT AFTER FINAL ACTION

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Post Office Box 7068
Pasadena, CA 91109-7068
February 3, 2010

Commissioner:

In response to the Office action of August 3, 2009, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 6 of this paper.